

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Peter Silverman                      Art Unit: Unknown  
Serial No.:                      Examiner: Unknown  
Filed : September 18, 2003  
Title : MULTILAYER COATINGS FOR EUV MASK SUBSTRATES

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

## INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Applicants call attention to the attached Information Disclosure Statement and documents listed on form PTO-1449.

This filing is being made with the filing of the application. No fee is required.

The documents are in the English language; hence no concise explanation is necessary per Rule 98(a)(3).

Consideration of the foregoing and enclosures plus the return of a copy of the enclosed form PTO-1449 with the Examiner's initials in the left column per MPEP 609 are earnestly solicited along with an early action on the merits.

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Respectfully submitted,

/BY

DWIGHT THOMPSON

REG. NO. 53,688

Date: 09/18/03

*Dwight Thompson - for Scott Harris*

Scott C. Harris

Reg. No. 32,030

Attorney for Intel Corporation

Fish & Richardson P.C.  
PTO Customer No. 20985  
4350 La Jolla Village Drive, Suite 500  
San Diego, CA 92122  
Telephone: (858) 678-5070  
Facsimile: (858) 678-5099

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Substitute Form PTO-1449 (Modified)  <b>Information Disclosure Statement by Applicant</b> (Use several sheets if necessary)  (37 CFR §1.98(b))	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. <b>10559-870001</b>	Application No.
	Applicant <b>Peter Silverman</b>		
	Filing Date <b>September 18, 2003</b>	Group Art Unit	

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						
	AE						

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AF							
	AG							
	AH							
	AI							
	AJ							

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
	AK	Claude Montcalm, "In situ Characterization of EUV Multiplayer Mirrors Deposited by UHV Magnetron Sputterin", Information Science and Technology, Lawrence Livermore National Laboratory, University of California, Livermore, CA
	AL	Rick Tejeda, "EUV Mask Modeling", Computational Mechanics Center, Mechanical Engineering Department, University of Wisconsin-Madison, 03/04/1999
	AM	John E. Bjorkholm, "EUV Lithography-The Successor to Optical Lithography?", Intel Technology Journal Q#98, pages 1-8
	AN	Mathieu F. Bal et al., "the Influence of Multilayers on the Optical Performance of Extreme Ultra Violet Projection Systems", Optics Research Group, Delft University of Technology
	AO	A. Mikkelsen et al., "Mounting Effects on Image Placement Errors", Computational Mechanics Center, Mechanical Engineering Department, University of Wisconsin-Madison
	AP	S. Wolf et al., "Silicon Processing for the VLSI Era", Volume 1; Process Technology, Second Edition, Lattice Press, Sunset Beach, CA, pages 444-450, 468-483, 777, 649-650, and 666

Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	